

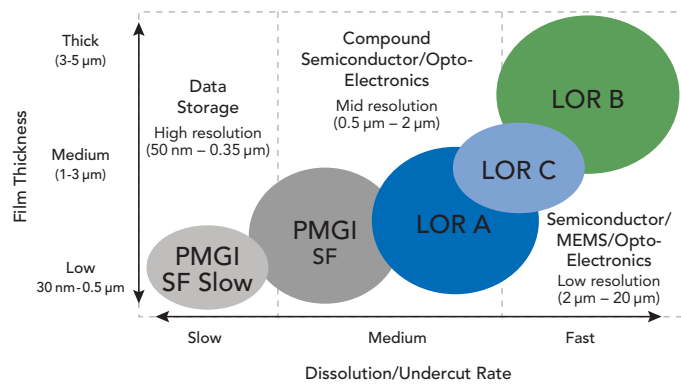
PMGI/LOR

Resists for Bi-layer Lift-off Processing

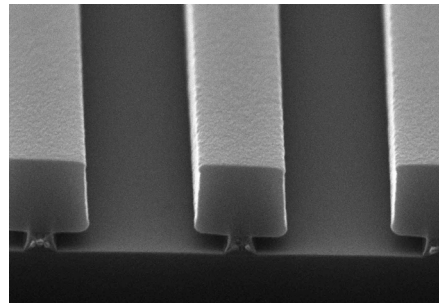
FEATURES

- Submicron metallized patterning
- Ultra thick metallized patterning
- Compatible with sputtered or evaporated metal
- Compatible with most photoresists
- Single aqueous develop step
- Superb undercut control
- High T_g, strips easily in most resist removers

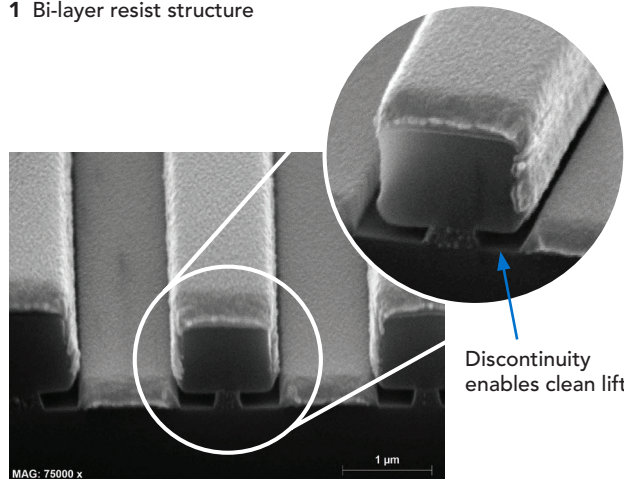
PRODUCT RANGE



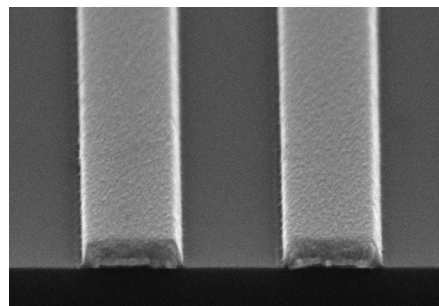
BI-LAYER LIFT-OFF PROCESS



1 Bi-layer resist structure



2 Au metallization over bi-layer resist structure



3 Au metallization after resist lift-off